**IN THE CLAIMS:** 

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Please amend the claims to read as follows:

1. (Original) A process for producing a poly(methyl methacrylate)-metal cluster

composite, which comprises bringing poly(methyl methacrylate) into contact with a heavy metal

compound under ultraviolet irradiation.

2. (Original) A process for producing a poly(methyl methacrylate)-metal cluster

composite, which comprises bringing a poly(methyl methacrylate) basal plate having an

ultraviolet-irradiated portion into contact with vapor of a heavy metal compound to form heavy

metal nanoparticles on the ultraviolet-irradiated portion.

3. (Original) The process for producing a poly(methyl methacrylate)-metal cluster

composite according to claim 1 or 2, wherein the heavy metal compound is selected from

acetylacetonate complexes of palladium, cobalt or copper.

4. (Original) The process for producing a poly(methyl methacrylate)-metal cluster

composite according to claim 2, wherein the poly(methyl methacrylate) basal plate is brought

into contact with vapor of the heavy metal compound in a non-oxidizing atmosphere.

5. (Original) The process for producing a poly(methyl methacrylate)-metal cluster

composite according to claim 2, wherein the poly(methyl methacrylate) basal plate is brought

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into contact with vapor of the heavy metal compound at a temperature of glass transition temperature of the poly(methyl methacrylate) basal plate or higher.

- 6. (Currently Amended) The process for producing a poly(methyl methacrylate)-metal cluster composite according to any one of claims 2 to 5 claim 2, wherein the ultraviolet-irradiated portion is formed in a predetermined pattern.
- 7. (Original) The process for producing a poly(methyl methacrylate)-metal cluster composite according to claim 6, wherein the predetermined pattern is formed by masking.
- 8. (Currently Amended) A patterning material which comprises a poly(methyl methacrylate)-metal cluster composite obtainable by the process according to any one of claims 1 to 7 claim 1 or 2.
- 9. (Original) A method for patterning metal nanoparticles having a predetermined form on a poly(methyl methacrylate) basal plate, which comprises forming a masking portion having a predetermined form on the poly(methyl methacrylate) basal plate having an ultravioletirradiated portion, and then bringing the plate into contact with vapor of a heavy metal compound to form metal nanoparticles on a non-masking portion.